#### TECHNICAL SPECIFICATIONS OF THE EQUIPMENTS TO BE PROCURED

# A. Specifications for Thin Film Coating System that has RF-DC Sputtering and Thermal Evaporation are as follows:

- 1. RF-DC sputtering:
- a. Vacuum Chamber:
  - -Should be made of SS-304 material with provision for water cooling.
  - -Dimensions not less than 40 cm Dia X 40 cm Width X 50 cm height.
  - -Chamber should be suitable for magnetron mounting, thermal source and source shutter
  - -Should have provision to prevent debris to go into the vacuum valve and electrodes.
  - -Easily cleanable
  - -Built to hold a vacuum level lower than 10-6 mbar.
  - -Provision to rotate the targets and fixing suitable metal masks

### b. Vacuum generation:

- -Should have dry scroll pump with displacement capacity of atleast 10 m<sup>3</sup>/h and turbo molecular pump with pumping speed of 400 lt/s for nitrogen
- -Should have liquid nitrogen trap
- -All the vacuum lines and valves should be made of stainless steel (non-corrosive) materials.
- -Vacuum generation should be better than 10-6 mbar
- -Appropriate vacuum gauges should be provided

#### c. Sources for Magnetron

- -Provision to hold two numbers of 2" diameter sputter sources
- -High power Nd-Fe-B magnets

#### d. Power Supply

- -For DC sputtering, suitable power supply should be provided
- -For RF magnetron, atleast 300W RF power at 13.56 MHz should be provided

#### e. Substrate holder

- -Should be able to accommodate 4" substrate
- -Motorized rotation controllable from outside.
- -Temperature upto 800°C with controller
- f. RF/DC selector switch with 2-in-2-out RF/DC switch box to direct the RF/DC power in between two magnetrons.
- g. Mass flow controllers for Oxygen/ Nitrogen and Argon
- h. Thin film deposition monitor
- i. External water chilling unit
- j. Built-in but independent Thermal evaporation facility with separate controls and power supply system
- k. Should have very low leak rate less than of 3 x10<sup>-9</sup> std. cc/sec.

#### 2. Thermal Evaporation:

- a. Glass Chamber with Vacuum generated by TurboMolecular pump with pumping speed of 400 lt/s for nitrogen with liquid nitrogen trap backed by Scroll pump with displacement capacity of atleast 10 m³/h
- b. Must have substrate heating arrangement

- c. Boats/ holders for the evaporation sources
- d. Thin film deposition monitor
- e. All required accessories, cooling systems etc. should be supplied

## 3. General Terms

- a. Installation and Standard, Additional warranty for 2 years must be Quoted on yearly basis.
- b. Should provide complete set of operating manual should be provided & training for our personnel
  - c. The Tender should provide onsite support service.